

**FIRST
INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

Sheet 1

1

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3

Complete if Known

Application Number	10/764,407
Filing Date	January 23, 2004
First Named Inventor	Shenggao Liu et al.
Examiner Name	

Attorney Docket Number 005950-844

OCT 15 2004

U.S. PATENT DOCUMENTS

Examiner Initials	Document Number	Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Issue/Publication Date (MM-DD-YYYY)
CH	5,166,313	528/344	Archibald et al.	11/24/92
CH	5,399,647	526/297	Nozaki	03/21/95
CH	5,621,019	522/49	Nakano et al.	04/15/97
CH	5,665,518	430/270.1	Maeda et al.	09/09/97
CH	5,691,111	430/270.1	Iwasa et al.	11/25/97
CH	5,756,850	568/75	Iwasa et al.	05/26/98
CH	5,929,271	560/126	Hada et al.	07/27/99
CH	6,042,991	430/285.1	Aoai et al.	03/28/00
CH	6,071,670	430/270.1	Ushirogouchi et al.	06/06/00
CH	6,077,644	430/270.1	Hada et al.	06/20/00
CH	6,087,063	430/270.1	Hada et al.	07/11/00
CH	6,103,445	430/270.1	Wilson et al.	08/15/00
CH	6,124,074	430/270.1	Varanasi et al.	09/26/00
CH	6,136,501	430/270.1	Trefonas, III et al.	10/24/00
CH	6,200,724	430/270.1	Namiki et al.	03/13/01
CH	6,200,728	430/270.1	Cameron et al.	05/01/01
CH	6,225,019	430/270.1	Matuda et al.	05/01/01
CH	6,225,476	549/323	Hada et al.	05/29/01
CH	6,238,842	430/281.1	Sato et al.	06/12/01
CH	6,245,485	430/288.1	Aoai et al.	06/26/01
CH	6,251,569	430/325	Angelopoulos et al.	07/31/01
CH	6,268,106	430/270.1	Park et al.	09/18/01
CH	6,291,130	430/270.1	Kodama et al.	10/23/01
CH	6,306,554	430/270.1	Barclay et al.	11/06/01
CH	6,313,327	552/553	Seo et al.	02/05/02
CH	6,344,590	568/591	Nakano et al.	04/30/02
CH	6,380,270	521/50.5	Yates	05/07/02
CH	6,383,713	430/270.1	Uetani et al.	05/14/02
CH	6,388,101	549/318	Hada et al.	05/21/02
CH	6,391,520	430/270.1	Nakano et al.	06/11/02
CH	6,403,280	430/270.1	Yamahara et al.	06/11/02
CH	6,403,823	560/116	Hasegawa et al.	07/09/02
CH	6,416,925	430/270.1	Aoai et al.	08/27/02
CH	6,440,636	430/270.1	Ushirogouchi et al.	10/08/02
CH	6,462,158	526,282	Miwa et al.	10/15/02
CH	6,465,137	430/5	Watanabe et al.	11/12/02
CH	6,479,211	430/270.1	Sato et al.	11/26/02
CH	6,486,330	549/270	Nakano	12/03/02
CH	6,489,082	430/313	Hattori et al.	12/10/02
CH	6,492,086	430/270.1	Barclay et al.	12/24/02
CH	6,498,226	528/170	Cheng et al.	02/11/03
CH	6,517,991	430/270.1	Kodama et al.	04/15/03
CH	6,548,221	430/270.1	Uetani et al.	04/22/03
CH	6,552,143	526/271	Funaki et al.	04/29/03
CH	6,555,289	430/270.1	Sasaki et al.	05/13/03
CH	6,562,554	430/326	Varanasi et al.	05/20/03
CH	6,566,038	430/270.1	Nishi et al.	

Examiner Signature

Date Considered

9-8-05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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Sheet

2

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U.S. PATENT DOCUMENTS

Examiner Initials	Document Number	Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Issue/Publication Date (MM-DD-YYYY)
CH	2001/0026901	430/270.1	Maeda et al.	10/04/01
CH	2002/0016516	568/818	Nakano et al.	02/07/02
CH	2002/0037472	430/270.1	Zampini et al.	03/28/02
CH	2002/0048720	430/270.1	Sasaki et al.	04/25/02
CH	2002/0064727	430/270.1	Sato	05/30/02
CH	2002/0076543	428/315.9	Sikonia	06/20/02
CH	2002/0099147	525/329.7	Yoshida et al.	07/25/02
CH	2002/0120090	528/170	Cheng et al.	08/29/02
CH	2002/0123010	430/325	Angelopoulos et al.	09/05/02
CH	2002/0046516	568/818	Nakano et al.	02/07/02
CH	2002/0169266	526/281	Funaki et al.	11/14/02
CH	2002/0177743	585/16	Dahl et al.	11/28/02
CH	2002/0182360	428/40.5	Koshiyama et al.	12/05/02
CH	2002/0182534	430/270.1	Varanasi et al.	12/05/02
CH	2002/0187420	430/270.1	Barclay et al.	12/12/02
CH	2003/0008241	430/287.1	Sato et al.	01/09/03
CH	2003/0017415	430/287.1	Kodama et al.	01/23/03
CH	2003/0017635	438/29	Apen et al.	02/13/03
CH	2003/0031789	427/248.1	Bedwell et al.	02/13/03
CH	2003/0031949	430/270.1	Barclay et al.	02/13/03
CH	2003/0031950	430/270.1	Uenishi et al.	03/06/03
CH	2003/0044717	430/270.1	Kodama	03/06/03
CH	2003/0044718	430/270.1	Kodama et al.	03/27/03
CH	2003/0059710	430/270.1	Inoue	04/03/03
CH	2003/0064327	430/325	Rottstegge	04/10/03
CH	2003/0068585	430/324	Rottstegge	04/17/03
CH	2003/0073027	430/270.1	Namiki et al.	06/20/02
CH	2002/0076543	428/315.9	Sikonia	04/24/03
CH	2003/0077540	430/270.1	Kodama et al.	04/24/03
CH	2003/0077543	430/287.1	Sato	06/05/03
CH	2003/0102285	216/41	Nozaki et al.	06/05/03
CH	2003/0105264	528/31	Bedwell et al.	06/12/03
CH	2003/0108809	430/171	Sato	09/05/02
CH	2003/0123010	430/325	Angelopoulos et al.	07/17/03
CH	2003/0134225	430/270.1	Fujimori et al.	08/07/03
CH	2003/0148206	430/127	Kodama	08/07/03
CH	2003/0148210	430/270.1	Funaki et al.	08/07/03

44

Examiner Signature		Date Considered	9/9/05
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FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT <small>(use as many sheets as necessary)</small>				<i>Complete if Known</i>		
Substitute for form 1449A/PTO & 1449B/PTO		Application Number		10/764,407		
		Filing Date		January 23, 2004		
		First Named Inventor		Shenggao Liu et al.		
		Examiner Name				
Sheet	3	of	3	Attorney Docket Number		005950-844

NON-PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
GJ	LIAW, Der-Jang, "Synthesis and characterization of new polyamides and polyimides prepared from 2,2-bis[4-(4-aminophenoxy)phenyl]adamantane," <u>Macromol. Chem. Phys.</u> 200, No. 6, pp. 1326-1332 (1999)
GJ	NOZAKI, Koji et al., "High-Performance Resist Materials for ArF Excimer Laser and Electron Beam Lithography," <u>FUJITSU Sci Tech. J.</u> , 38, 1, pp. 3-12 (June 2002)
GJ	PADMANABAN, Munirathna, et al., "Etch Properties of 193nm Resists: Issues and Approaches," <u>Journal of Photopolymer Science and Technology</u> , Vol 15, No. 3 (2002), pp. 521-528
GJ	PADMANABAN, Munirathna, et al., "Layer-Specific Resists for 193nm Lithography," <u>Journal of Photopolymer Science and Technology</u> , Vol. 13, No. 4 (2000) pp. 607-616
GJ	PANIEZ, P. J., et al., "Thermal Phenomena in Acrylic 193 nm Resists," <u>SPIE Conferences on Advances in Resist Technology and Processing XVI</u> , Santa Clara, CA, <u>SPIE</u> Vol. 3678 pp. 1352-1363
GJ	SHIDA, Naomi, "Advanced Materials for 193-nm Resists," <u>Journal of Photopolymer Science and Technology</u> , Vol. 13, No. 4 (2000) pp. 601-606
GJ	USHIROGOUCHI, Tohru, et al., "Advanced Materials for 193-nm Resists," In <u>Advances in Resist Technology and Processing XVII</u> , Francis M. Houlahan, Editor, <u>Proceedings of SPIE</u> Vol. 3999 (2000) pp. 1147-1156

Examiner Signature *John H. Muller* Date Considered *10/10/05* Performance with M.R.E.P. § 609. Draw line through citation if not in

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